

	Hits	Search Text	DBs
27	67	(photoreact\$4 or photocur\$5 or photosensitive or photoactiv\$5 or (light near6 sensit\$6)) and ((photoreactive or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4) same (pattern or void or interstitial or (line near9 space) or grat\$4)) and ((grat\$4 or waveguide) same (deposit\$4 or coat\$4 or form\$4 or film\$4) same (zirconia or alumina or silica or (metal\$4 near9 (complex\$3 or salt or oxide)) or semiconductor or silicon or Si) same treat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
28	26	(photoreact\$4 or photocur\$5 or photosensitive or photoactiv\$5 or (light near6 sensit\$6)) and ((photoreactive or photosensitive) same (expos\$4 or irradiat\$4 or illuminat\$4) same (pattern or void or interstitial or (line near9 space) or grat\$4) same (deposit\$4 or coat\$4 or form\$4 or film\$4) same (zirconia or alumina or silica or (metal near9 oxide) or semiconductor) same treat\$4) and interference and ((develop\$4 or ablat\$4 or pyrolyss\$3) same (pattern or relief or structure))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB